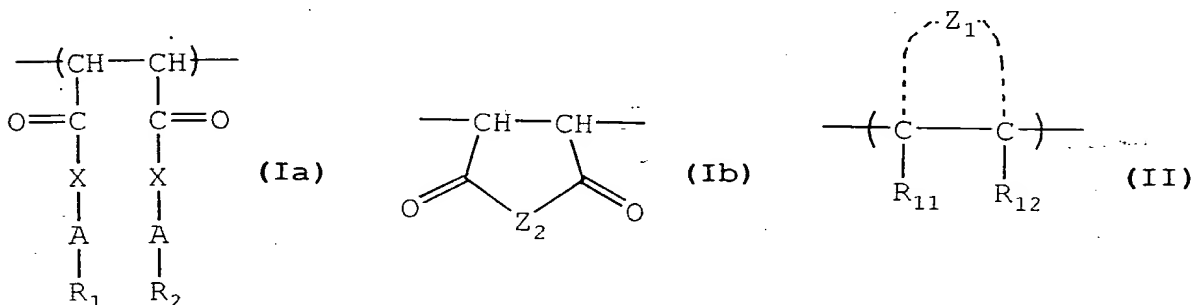


# ABSTRACT OF THE DISCLOSURE

The present invention provides a positive photoresist composition for far ultraviolet exposure, which comprises a polymer having at least one of a repeating unit represented by formula (Ia) and a repeating unit represented by formula (Ib), and a repeating unit represented by formula (II), and having a group capable of decomposing by the action of an acid:



wherein  $R_1$  and  $R_2$  each represents hydrogen atom, a cyano group, a hydroxyl group,  $-\text{COOH}$ ,  $-\text{COOR}_5$ ,  $-\text{CO-NH-R}_6$ ,  $-\text{CO-NH-SO}_2\text{-R}_6$ , an alkyl group, an alkoxy group, a cyclic hydrocarbon group or a  $-\text{Y}$  group,  $X$  represents  $-\text{O}-$ ,  $-\text{S}-$ ,  $-\text{NH}-$ ,  $-\text{NHSO}_2-$  or  $-\text{NHSO}_2\text{NH}-$ ,  $A$  represents a single bond or a divalent linking group,  $Z_2$  represents  $-\text{O}-$  or  $-\text{N(R}_3)-$ ,  $R_{11}$  and  $R_{12}$  each represents a hydrogen atom, a cyano group, a halogen atom or an alkyl group,  $Z_1$  represents an atomic group necessary for forming an alicyclic structure which contains two bonded carbon atoms ( $\text{C-C}$ ), and  $Y$ ,  $R_3$ ,  $R_5$  and  $R_6$  are as defined in the specification.